

# **AEC/APC Symposium Asia 2011**

Join us to make the move to more intelligent manufacturing Wednesday, November 9, 2011
 National Center of Sciences Building, Tokyo, Japan

## **AEC/APC Symposium Asia 2011 in Tokyo, Japan**

## **Important Date:**

July 15
Extended abstract
submission due
Aug. 23
Notification of abstract
acceptance

Oct. 19 Presentation materials due

In recent years, remarkable achievements have been realized in the field of AEC/APC which can be called the core of scientific semiconductor production technology. It is an important factor holding the key to improving the efficiency of equipment and yield enhancement in leading-edge LSI manufacturing.

Experts will present the results of advanced development in the field of AEC/APC and exchange knowledge and technology. We look forward to receiving additional abstracts and publishing more articles, including proposals for the future.

This call for papers is directed to the semiconductor and photovoltaic community, and other relevant industries, such as display, LED, lamps or glass. Other industries employing AEC/APC may also submit abstracts. The conference, focused on current challenges and future needs beyond AEC/APC, will be built around sessions of the following topics:

#### **Executive Committee**

Co-Chairs:

Bradley Van Eck/ISMI Shigeru Kobayashi/Renesas Elec. Vice chair:

Koji Maekawa/PDF Solutions

Kensuke Uriga/Dura Systems Toshiyuki Uchino/Renesas Elec.

## **Program Committee**

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Toshiya Hirai / Sony Semiconductor Kyushu Koichi Sakamoto/ Tokyo Electron

Takashi Kurosawa / Yamatake

Hisato Tanaka/ Tokyo Electron Miyagi

Process Level Topics

### **Equipment and Process Control methodology:**

Fault detection and classification Statistical process control Run-to-run control

Enhanced equipment quality assurance

#### **Productivity & Tool Optimizations:**

Throughput enhancement Uptime ratio improvement Cost reduction

Non-product wafer reduction

Maintenance

#### **Model-based Process Control:**

Physical and chemical process model

Model-based sensors

Soft sensor Virtual metrology Sampling plan

### **Tool Data Analysis:**

Data collection Data acquisition Failure and Yield Analysis Statistical approaches Non-statistical approaches

## **Fab Level Topics**

#### Data Analysis, Modeling and Visualization:

Data collection
Correlation analysis

Mathematical methods and model creation,

Novel methods of data visualization and

Data analysis

## **Control Methods:**

Run to run Real-time control Control algorithms

#### **Benefit of APC Application:**

CoO OEE Yield Productivity

Environment, safety and health

### **APC Integration:**

Fab automation Scheduling and dispatch Yield management Design for manufacturing Supply chain management

#### IT Infrastructure for APC:

Fab-wide APC

Tool interfaces and communication Innovative IT solutions

#### APC Strategy:

Future Needs and opportunities

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## **Online Abstract Submission Procedure:**

- Prospective authors are requested to submit the abstract through web browser, consisting of exactly two pages of A4-paper size.
- The first page consists of the text (max of 1,000 words) and the second page consists of figures, supporting data, charts, photos and drawings.
- Only MS Word and JPEG/GIF files are compatible.
- The abstract must be written in English, using the online abstract submission form.
- Submit electronically before July 15, 2011.

<u>Information, templates, and other details are available on the website:</u>
<a href="http://www.semiconportal.com/AECAPC/cfp.html">http://www.semiconportal.com/AECAPC/cfp.html</a>